

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	8	US-3974382-\$.DID. OR US-4402600-\$.DID. OR US-5530616-\$.DID. OR US-5656093-\$.DID.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 15:49
S2	2	("6217655").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/12/29 19:07
S3	2	("5982607").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/12/29 19:13
S4	5	pimple adj plate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/29 19:13
S5	13462	((250/492.2) or (250/440.11) or (361/234) or (279/128) or (279/3) or (248/683) or (355/53) or (355/72) or (355/73) or (355/75) or (355/76) or (378/34) or (378/20) or (378/177) or (378/187)).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/12/30 10:59
S6	2781	S5 and lithography	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 10:59
S7	2639	S6 and (mask or reticle or substrate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 11:00
S8	316	S7 and (pliable or compliant or flexible or deformable)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 11:02

S9	21	("4480284" "4724510" "5166856" "5179498" "5191506" "5255153" "5324053" "5486974" "5486975" "5522131" "5532903" "5539179" "5560780" "5583736" "5631803" "5646814" "5691876" "5745331" "5764471" "5777838").PN. OR ("6117246"). URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2004/12/30 12:13
S10	2	("5532903").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/12/30 14:59
S11	19	("3974382" "4610020" "5275683" "5382311").PN. OR ("5532903").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2004/12/30 14:59
S12	11	("3993509" "4184188" "4384918" "4551192" "5532903" "5583736" "5764471" "5777838" "5851641" "5883778").PN. OR ("6215642"). URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2004/12/30 15:11
S13	2	("6480260").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/12/30 15:49
S14	5	("4716299" "4749867" "5137349" "6118515").PN. OR ("6480260").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2004/12/30 15:49
S15	70	("4184188" "4361643" "4384918" "4502094" "4599970" "4603466" "5117121" "5192371" "5376180" "5382311" "5447595" "5456756" "5463526" "5474614" "5528451" "5530616" "5531835" "5560780" "5583736").PN. OR ("5656093").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2004/12/30 16:05
S16	36	("4502094" "4565601" "4724510" "4962441" "5104834" "5160152" "5191506" "5213349" "5267607" "5306895" "5315473" "5350479").PN. OR ("5530616").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2004/12/30 16:21
S17	1	"4610020".PN.	USPAT; USOCR	OR	ON	2004/12/30 16:28

S18	1	"5382311".PN.	USPAT; USOCR	OR	ON	2004/12/30 16:28
S19	1	"3974382".PN.	USPAT; USOCR	OR	ON	2004/12/30 16:28
S20	13462	((250/492.2) or (250/440.11) or (361/234) or (279/128) or (279/3) or (248/683) or (355/53) or (355/72) or (355/73) or (355/75) or (355/76) or (378/34) or (378/20) or (378/177) or (378/187)).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/12/30 16:34
S21	2781	S20 and lithography	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 16:34
S22	2639	S21 and (mask or reticle or substrate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 16:34
S23	316	S22 and (pliable or compliant or flexible or deformable)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 16:35
S24	2	S23 and besel	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 16:37
S25	1	S20 and (besel adj point)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 16:39
S26	36	(besel adj point)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 17:00
S27	96	S20 and kinematic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 17:00

S28	84	S27 and three	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 17:14
S29	54	kinematic and bessell	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 17:15
S30	54	kinematic and bessell	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 17:28
S31	3	kinematically and (bessell or bessell)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/30 17:29

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Search Results - Record(s) 1 through 2 of 2 returned.

☐ 1. Document ID: [EP 1107066 A2](#)

Using default format because multiple data bases are involved.

L1: Entry 1 of 2

File: EPAB

Jun 13, 2001

PUB-NO: EP001107066A2

DOCUMENT-IDENTIFIER: [EP 1107066 A2](#)

TITLE: Lithographic apparatus with mask clamping apparatus

PUBN-DATE: June 13, 2001

INVENTOR-INFORMATION:

NAME

COUNTRY

DONDERS, SJOERD NICOLAAS LAMBER

NL

VAN, EMPEL TJARKO ADRIAAN RUDOL

NL

INT-CL (IPC): [G03 F 7/20](#)

EUR-CL (EPC): [G03F007/20](#)

Full	Title	Citation	Front	Review	Classification	Date	Reference	Sequences	Attachments	Claims	KMC	Drawings
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☐ 2. Document ID: TW 504605 A, [EP 1107066 A2](#), JP 2001196303 A, KR 2001061974 A, US 6480260 B1

L1: Entry 2 of 2

File: DWPI

Oct 1, 2002

DERWENT-ACC-NO: 2002-123948

DERWENT-WEEK: 200337

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TITLE: Lithographic projector for imaging mask pattern onto substrates used during manufacture of integrated circuits includes mask table with mask compliant member that conforms to mask profile

INVENTOR: DONDEERS, S N L; VAN EMPEL, T A R

PRIORITY-DATA: 1999EP-0204103 (December 3, 1999)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
TW 504605 A	October 1, 2002		000	G03F009/00
EP 1107066 A2	June 13, 2001	E	012	G03F007/20
JP 2001196303 A	July 19, 2001		009	H01L021/027
KR 2001061974 A	July 7, 2001		000	G03F007/20
US 6480260 B1	November 12, 2002		000	G03B027/42

INT-CL (IPC): [A61 N 5/00](#); [G03 B 27/42](#); [G03 B 27/58](#); [G03 B 27/60](#); [G03 C 5/00](#); [G03 F 7/20](#); [G03 F 9/00](#); [H01 L 21/027](#)

NOVELTY - A lithographic projection has radiation system for supplying a projection beam of radiation, object table for holding a mask, second object table for holding a substrate, and projection system for imaging irradiated portions of the mask onto target portions of substrate. The mask table has compliant member(s) for holding the mask such that at least one member conform to the profile of the mask.

DETAILED DESCRIPTION - INDEPENDENT CLAIMS are also included for the following:

(A) a method of manufacturing a device using a lithographic projector involving providing a mask bearing a pattern to the first object table, providing a substrate with a radiation-sensitive layer to the second object table, and irradiating portions of the mask and imaging the irradiated portions onto the target portions of the substrate;

(B) a device manufactured by the process; and

(C) a mask table comprising compliant member (14). The mask is held during operation with the clamping device.

USE - The method is used for imaging mask pattern onto substrates during manufacture of integrated circuits, integrated optical systems, guidance and detection patterns for magnetic domain memories, liquid-crystal display panels, and thin-film magnetic heads.

ADVANTAGE - The members are compliant such that they accommodate flatness variations in the mask without deforming the mask.

DESCRIPTION OF DRAWING(S) - The figure shows a schematic view of an arrangement for supporting a mask using a compliant member.

Compliant members 14

Full	Title	Citation	Front	Review	Classification	Date	Reference	Sequences	Attachments	Claims	KWIC	Draw De
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Term	Documents
EP-1107066-\$	0
EP-1107066-A2	2
EP-1107066-\$.DID..PGPB,USPT,EPAB,JPAB,DWPI,TDBD.	2
(EP-1107066-\$.DID.).PGPB,USPT,EPAB,JPAB,DWPI,TDBD.	2

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